

Sub B1
Sub D17

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8. ~~The reticle sorter of claim 5, wherein the inspection system includes a tool for detection flaws in a reticle pattern.~~

9. The reticle sorter of claim 5, further including means for moving each cassettes from the input port to one of the one or more bays.

Sum 10. ~~The reticle sorter of claim 1, wherein the sorting system includes two or more docking locations.~~

Sum 11. The reticle sorter of claim 10, wherein the sorting system can move reticles between a first cassette in a first one of the two or more docking locations and a second cassette in a second one of the two or more docking locations.

12. The reticle sorter of claim 1, including three or more bays.

13. A semiconductor fabrication facility, including:
a plurality of photolithography exposure tools;
at least one reticle storage system including a buffer for storing cassettes;
and
one or more reticle sorters each associated with a group of one or more of the exposure tools, each reticle sorter including one or more docking locations each capable of holding a cassette having one or more reticles and sorting system for accessing and sorting reticles within each cassette.

14. The fabrication facility of claim 13, wherein the facility includes multiple reticle sorters at least one of which is associated with multiple exposure tools.

15. The fabrication facility of claim 13, wherein the one or more reticle sorters each send and receive cassettes to and from the associated group of one or more exposure tools and the reticle storage system.

17. A method of sorting cassettes in a semiconductor fabrication facility, comprising;

associating a group of one or more photolithography tools with a reticle sorter;

periodically moving one or more cassettes to the reticle sorter and sorting reticles within the one or more cassettes; and

periodically moving the one or more cassettes to a reticle storage system for storage.

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B2